

Title (en)

METHOD TO CREATE THIN FUNCTIONAL COATINGS ON LIGHT ALLOYS

Title (de)

VERFAHREN ZUR ERZEUGUNG DÜNNER FUNKTIONSSCHICHTEN AUF LEICHTMETALLLEGIERUNGEN

Title (fr)

PROCÉDÉ DE FORMATION DE REVÊTEMENTS FONCTIONNELS MINCES SUR DES ALLIAGES LÉGERS

Publication

EP 3500695 A4 20200325 (EN)

Application

EP 17841176 A 20170816

Priority

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- IB 2017054972 W 20170816

Abstract (en)

[origin: US2018051388A1] In example implementations, a method for producing a thin film coating is provided. The method includes pre-treating a substrate, placing the substrate in a bath comprising at least phosphoric acid and sulphuric acid to produce a thin anodized layer, rinsing the thin anodized layer in a solution, plating a surface of the thin anodized layer in an electro deposition bath following a plating current profile for a predetermined period, and increasing the plating current to the recommended bath plating current to produce the thin film coating having a desired initial coating thickness.

IPC 8 full level

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CPC (source: EP KR US)

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Citation (search report)

- [X1] JP 2011202194 A 20111013 - FUJIFILM CORP
- [A] US 2013164555 A1 20130627 - DING TING [CN]
- [A] GB 1423928 A 19760204 - COLALE R
- [A] EP 0368470 A1 19900516 - ALCAN INT LTD [CA]
- [A] EP 0490914 A1 19920624 - ALCAN INT LTD [CA]
- [A] GRIFFITHS ET AL: "An Aluminium Resist Substrate for Microfabrication by LIGA", SANDIA NATIONAL LABORATORIES, 1 April 2005 (2005-04-01), pages 1 - 26, XP055467691, Retrieved from the Internet <URL:https://digital.library.unt.edu/ark:/67531/metadc898399/m2/1/high_res_d/923166.pdf> [retrieved on 20180417]
- See references of WO 2018033862A1

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US 10519562 B2 20191231; **US 2018051388 A1 20180222**; AU 2017314185 A1 20190221; AU 2017314185 B2 20220714; CA 3073008 A1 20180222; CN 110114517 A 20190809; CN 110114517 B 20221213; EP 3500695 A1 20190626; EP 3500695 A4 20200325; JP 2019525011 A 20190905; JP 2022105544 A 20220714; JP 7389847 B2 20231130; KR 102502436 B1 20230222; KR 20190066004 A 20190612; TW 201819692 A 20180601; TW I762503 B 20220501; WO 2018033862 A1 20180222

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